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ABSTRACT

A projection exposure apparatus for transferring a pattern on a mask (1) onto a substrate (2), including
5 a projection optical system (3) having a first reflection optical element (312) for bending an optical axis (311), a first optical system arranged between the mask (1) and the first reflection optical element (312), and a second optical system (32)
10 arranged between the first reflection optical element (312) and the substrate (2); a frame (6) for integrally supporting a first barrel (4) for holding the first optical system (3) and a second barrel (5) for holding the second optical system (32), and a
15 connecting member (7) for connecting the first barrel (4) and the second barrel (5) at positions different from the frame (6), whereby a projection exposure apparatus reducing vibration of the barrels of the projection optical system and giving excellent imaging
20 characteristics is provided.

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